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WHAT IS CLAIMED IS:

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1. A thin film transistor array panel comprising:

an insulating substrate;

a gate wire formed on the insulating substrate and including a plurality of gate lines, a plurality of gate electrodes, and a plurality of gate pads connected to one ends of the gate lines;

a storage electrode wire formed on the insulating substrate and including a plurality of storage electrode lines and a plurality of storage electrodes;

a gate insulating layer formed on the gate wire and the storage electrode 10 wire;

a semiconductor layer formed on the gate insulating layer;

a data wire formed on the gate insulating layer and including a plurality of data lines insulated from and crossing over the gate lines, a plurality of source electrodes contacting the semiconductor layer in part, a plurality of drain electrodes facing the source electrodes and contacting the semiconductor layer in part, and a plurality of data pads connected to one ends of the data lines;

a passivation layer formed on the data wire;

a plurality of pixel electrodes formed on the passivation layer and electrically connected to the drain electrodes; and

a plurality of storage electrode connections formed on the passivation layer and connecting the storage electrode lines and the storage electrodes facing across the gate lines.

2. A thin film transistor array panel comprising: an insulating substrate;

a gate wire formed on the insulating substrate and including a plurality of gate lines, a plurality of gate electrodes, and a plurality of gate pads connected to one ends of the gate lines;

a storage electrode wire formed on the insulating substrate and including a plurality of storage electrode lines and a plurality of storage electrodes;

a gate insulating layer formed on the gate wire;

a semiconductor layer formed on the gate insulating layer;

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a data wire formed on the gate insulating layer and having a triple-layered structure including an amorphous silicon layer, an ohmic contact layer, and a metal layer, the data wire including a plurality of data lines, a plurality of source electrodes connected to the data lines, a plurality of drain electrodes facing the source electrodes, and a plurality of data pads;

- a passivation layer formed on the data wire;
- a plurality of pixel electrodes formed on the passivation layer and electrically connected to the drain electrodes; and
- a plurality of storage electrode connections formed on the passivation 10 layer and connecting the storage electrode lines and the storage electrodes facing across the gate lines.
 - 3. The thin film transistor array panel of claim 1 or 2, further comprising a plurality of color filters disposed between the data wire and the passivation layer.
- 15 4. The thin film transistor array panel of claim 1 or 2, further comprising a common bar connected to one ends of all the storage electrode lines.
 - 5. A thin film transistor array panel comprising: an insulating substrate;
- a first signal line formed on the insulating substrate and extending in a 20 transverse direction;
 - a second signal line formed on the insulating substrate and extending in a transverse direction;
 - a third signal line insulated from and crossing over the first and second and extending in a longitudinal direction;
- a plurality of pixel electrodes in pixel areas defined by intersections of the first signal lines and the third signal lines; and
 - a plurality of thin film transistors connected to the first signal lines, the third signal lines, and the pixel electrodes,
- wherein the second signal lines are connected to each other via connecting paths provided on the pixel areas.

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6. The thin film transistor array panel of claim 5, further comprising a common bar connecting one ends of the second signal lines.

7. A thin film transistor array panel comprising: an insulating substrate;

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- a plurality of first signal lines formed on the insulating substrate, extending in a transverse direction, and including a plurality of first signal pads;
 - a plurality of second signal lines formed on the insulating substrate and extending in a transverse direction;
- a plurality of third signal lines insulated from and intersecting the first 10 and the second signal lines, extending in a longitudinal direction, and including a plurality of third signal pads;
 - a plurality of pixel electrodes provided on pixel areas defined by intersections of the first signal lines and the third signal lines;
- a plurality of signal lines connected to the first signal lines, the third signal lines, and the pixel electrodes;
 - a first common bar connecting ends of the second signal lines located opposite the first signal pads; and
 - a second common bar connecting ends of the second signal lines located near the first signal pads,
- wherein the second the common bar has a width equal to or less than 150 microns.